

RF FPGA Annual Review:

Programmable RF Acoustic Filter Elements

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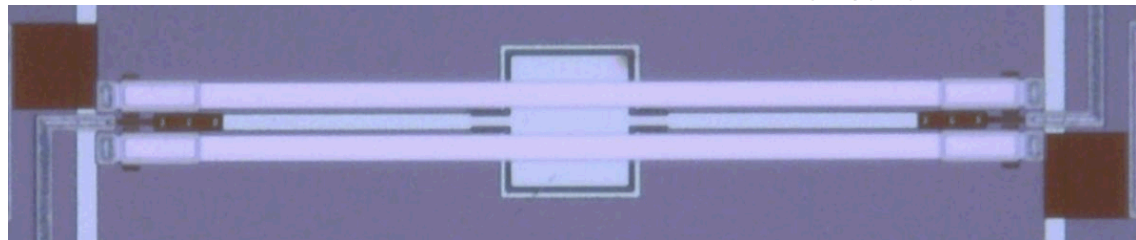
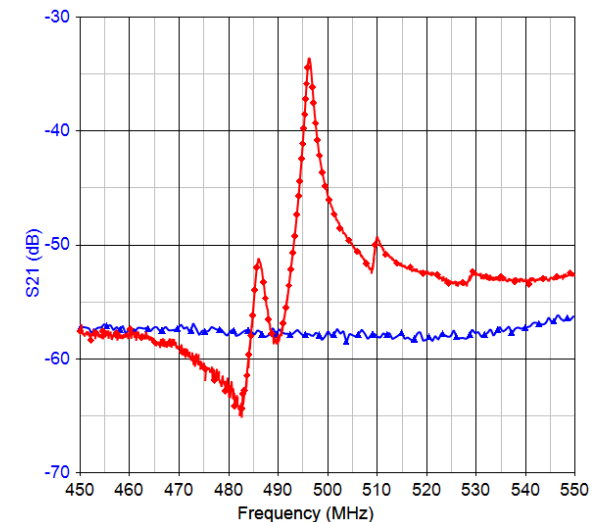
Sandia is a multiprogram laboratory operated by Sandia Corporation, a Lockheed Martin Company, for the United States Department of Energy's National Nuclear Security Administration under contract DE-AC04-94AL85000.





Overview

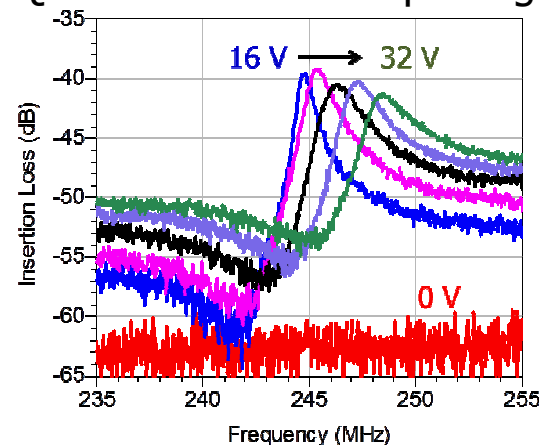
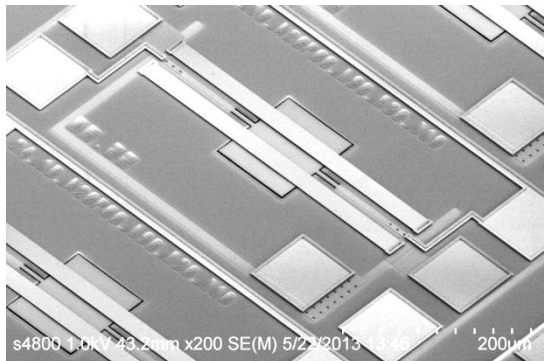
- **Project Objective: Demonstrate tuning and reconfigurability of high-Q resonators and filters using MEMS-switch based fingers.**
 - Designed project around demonstrating switch tuning; de-emphasized fixed filters
- **Current Status: Demonstrated on/off switching of piezoelectric filters using MEMS switches; many filter designs currently in fabrication.**
- **Outline**
 - Overview and Value Proposition
 - Technical Approach and Summary of Achievements
 - On / Off Resonator Concept
 - MEMS Switch Results
 - Resonator and Filter Modeling
 - Filter Design Concepts
 - Paths to Improved Performance
 - Assessment and Prospects





Project Goals

- **Description:** Fundamental research activity with goal of advanced technology demo and eventually transition.
- **Thesis Statement:** MEMS switches can modulate electrical coupling of piezoelectric resonators with negligible degradation, enable high-Q switched and reconfigurable filters, and achieve performance currently unobtainable with fixed acoustic resonator filters and/or tunable electromagnetic filters.
- **Technical Goals:**
 - Stage I: demonstrate and provide assessment of switched resonator tuning
 - Stage II: demonstrate five-state high-Q tunable filter
 - Stage III: demonstrate five-state high-Q tunable filter with packaging and control



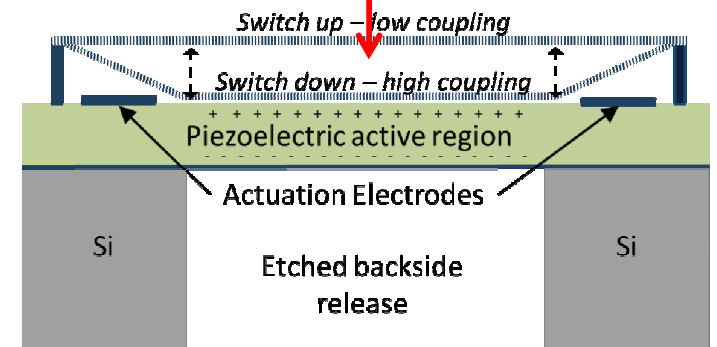
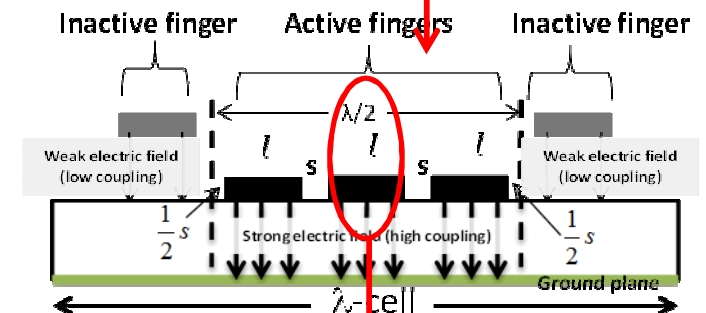
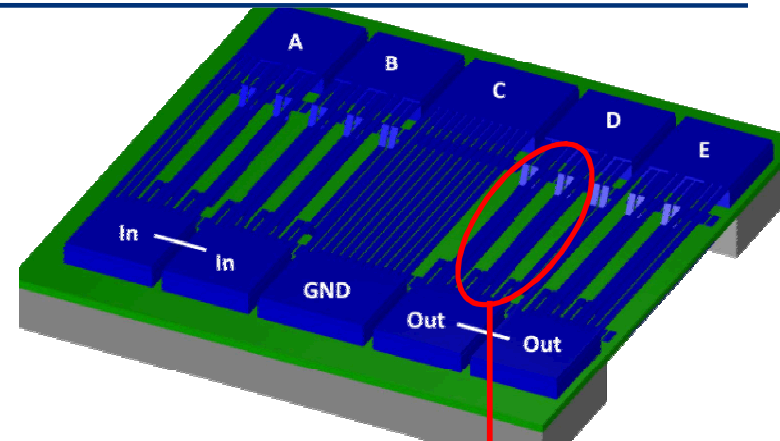


Value to the DARPA Mission

- **Maintain the technological superiority of the U. S. military**
 - If successful, this approach will enable switched and tunable filters that are an order of magnitude smaller than existing solutions in the kHz to low GHz range.
 - This will introduce new application- and standard- agility, and enhance the performance of future RF systems, and reduce supply chain complexity.
- **Prevent technological surprise**
 - Early investigation into this tunable filter approach provides insight and understanding into the capabilities and challenges of this technology.
- **Revolutionary, High-Payoff Research**
 - As this is the first time that this approach has been attempted, this research is revolutionary; if successful, it has the potential to revolutionize government and commercial RF front ends.
- **Bridging the gap between fundamental discoveries and use**
 - Maturation and transition of this fundamental research will provide a unique capability to the U. S. military and provide the first tunable, high-Q, filter technology.

Review of Technical Approach

- **Concept: Acoustic filter with multiple segments (five shown in figure)**
 - Blocks on end can be transducer or reflector (A,E)
 - Center block serves as coupling element (C)
 - Remaining blocks are transducers (B,D)
- **Tune response of each segment tuned by varying coupling of finger to piezoelectric film**
 - Use finite-element and coupling-of-modes modeling to predict and synthesize filter bandshape and response
- **Realize fingers using individually addressable MEMS devices**





Differentiating Technical Achievements

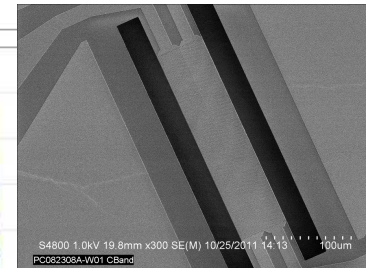
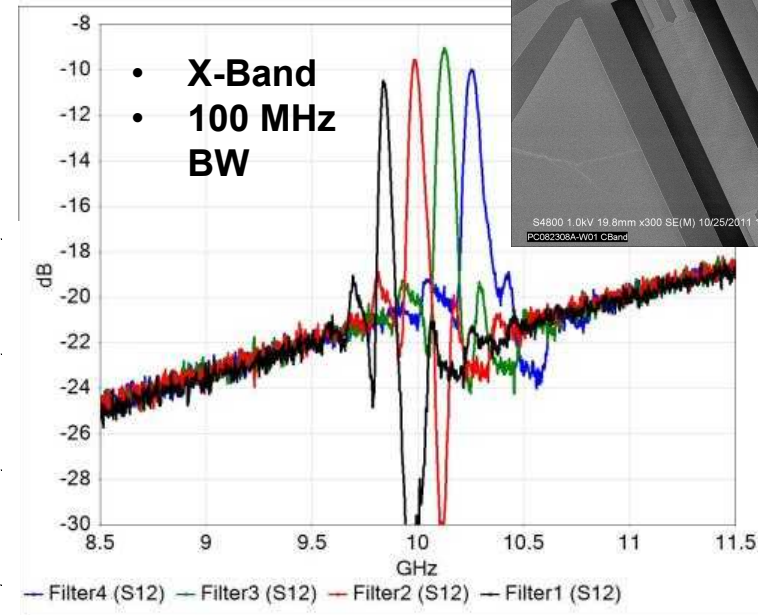
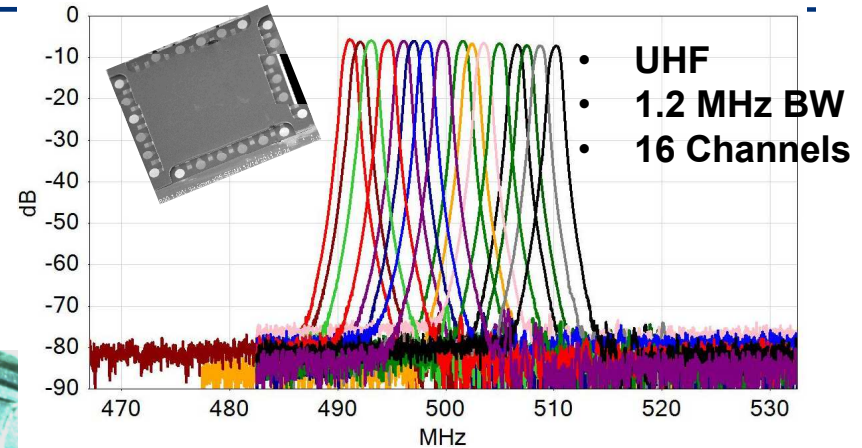
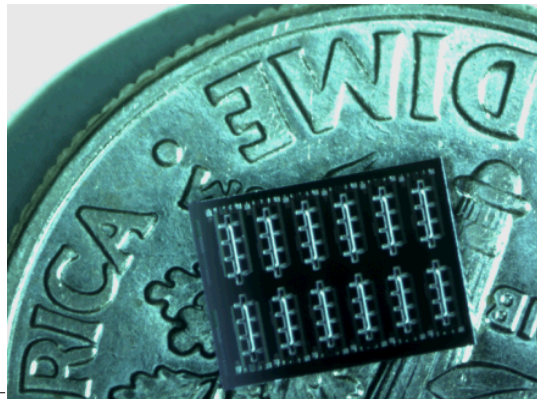
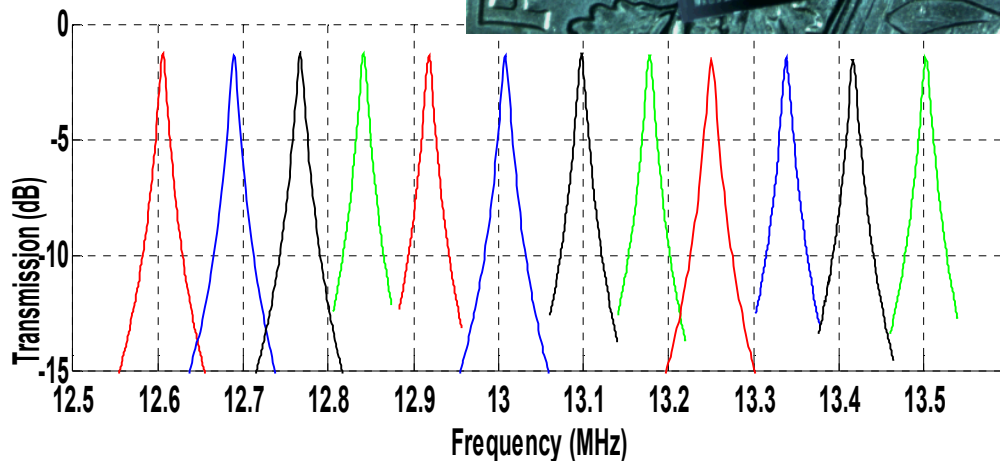
- **First use of MEMS switches for on/off switching of piezoelectric resonators/filters**
 - No demonstrations of switching MEMS piezoelectric resonators prior to this effort.
 - Current Result: On/Off switching demonstrated, reconfigurability not demonstrated yet but expected by end of Stage I.
- **On/off piezoelectric switching enables band- and shape- reconfigurable high-Q filters**
 - New class of piezoelectric filters with higher Q response than previously demonstrated by reconfigurable electromagnetic filters.
 - Current Result: Filters designed and wafers in fab, with measurements expected by the end of Phase I.
- **First integration of MEMS resonators and capacitive switches**
 - Enables reconfigurable piezoelectric and electromagnetic components on a single die, with potential for post-CMOS integration.
 - Current Result: Demonstrated integration of capacitive MEMS switches with AlN resonators in single integrated process flow. Continuously improving process for performance, yield, and reproducibility.



Context: Sandia AIN Filter Efforts

- Filter Banks for Cognitive and Multi-Band Radios
- Filter Arrays for Fast Spectrum Analysis
- Anti-Jam and Secure Adaptive RF Front-Ends
- Ultra Small Footprint (Wafer Level Packaging)
- Temperature Compensation
- High Rejection
- HF to X Band

- **HF-Band**
- **25 kHz BW**
- **12-Channels**

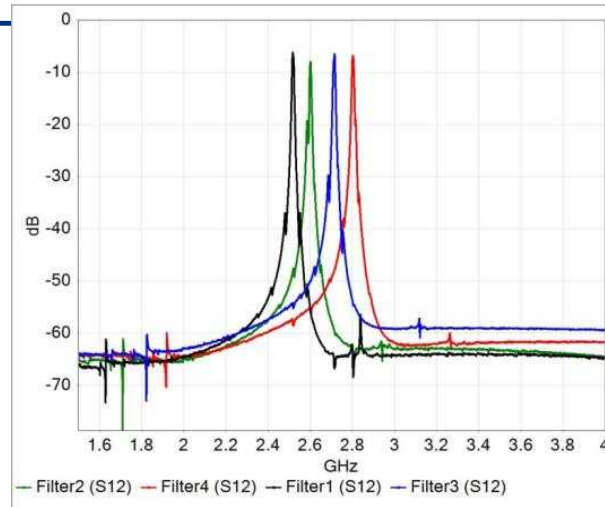




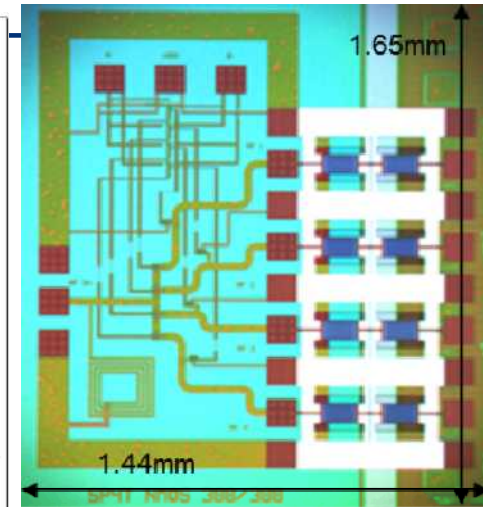
Switched Filter Arrays vs. RF FPGA

Traditional Approach

- Acoustic Filter for Each Frequency
- Selection Using CMOS Electronic Switches
- Large Area
- # of Filters (Bands) Limited by Switch $R_{on}C_{off}$

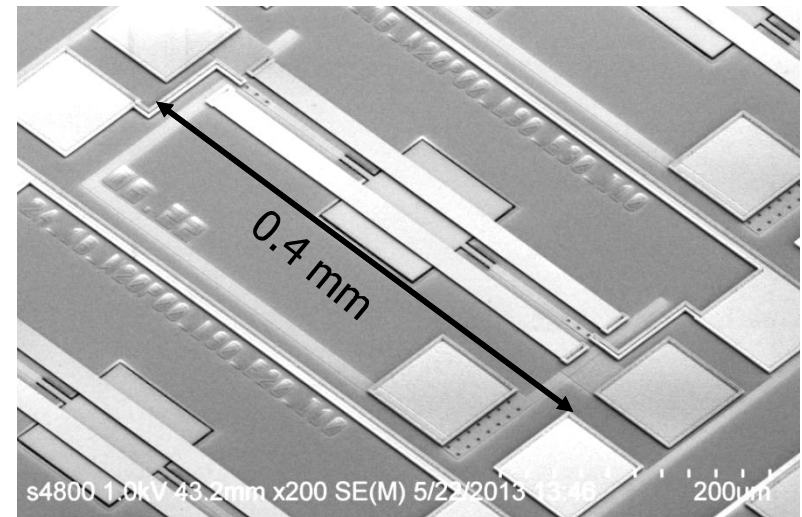


S-Band 4-Channel Switched Filter Array



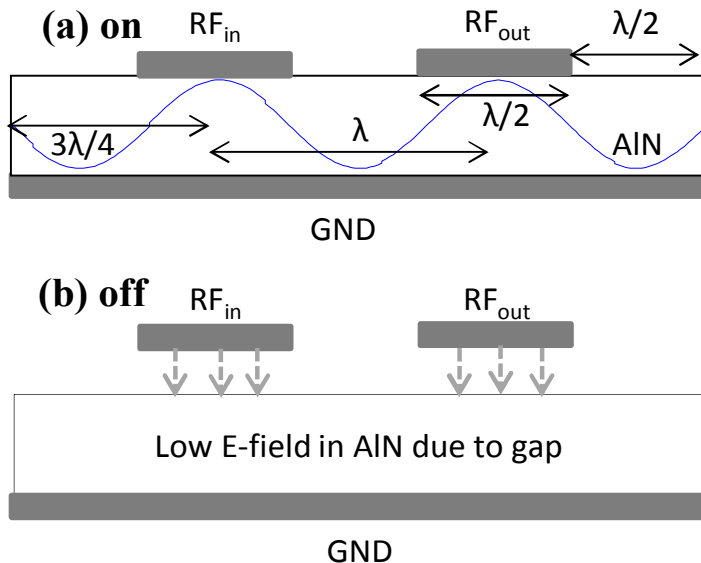
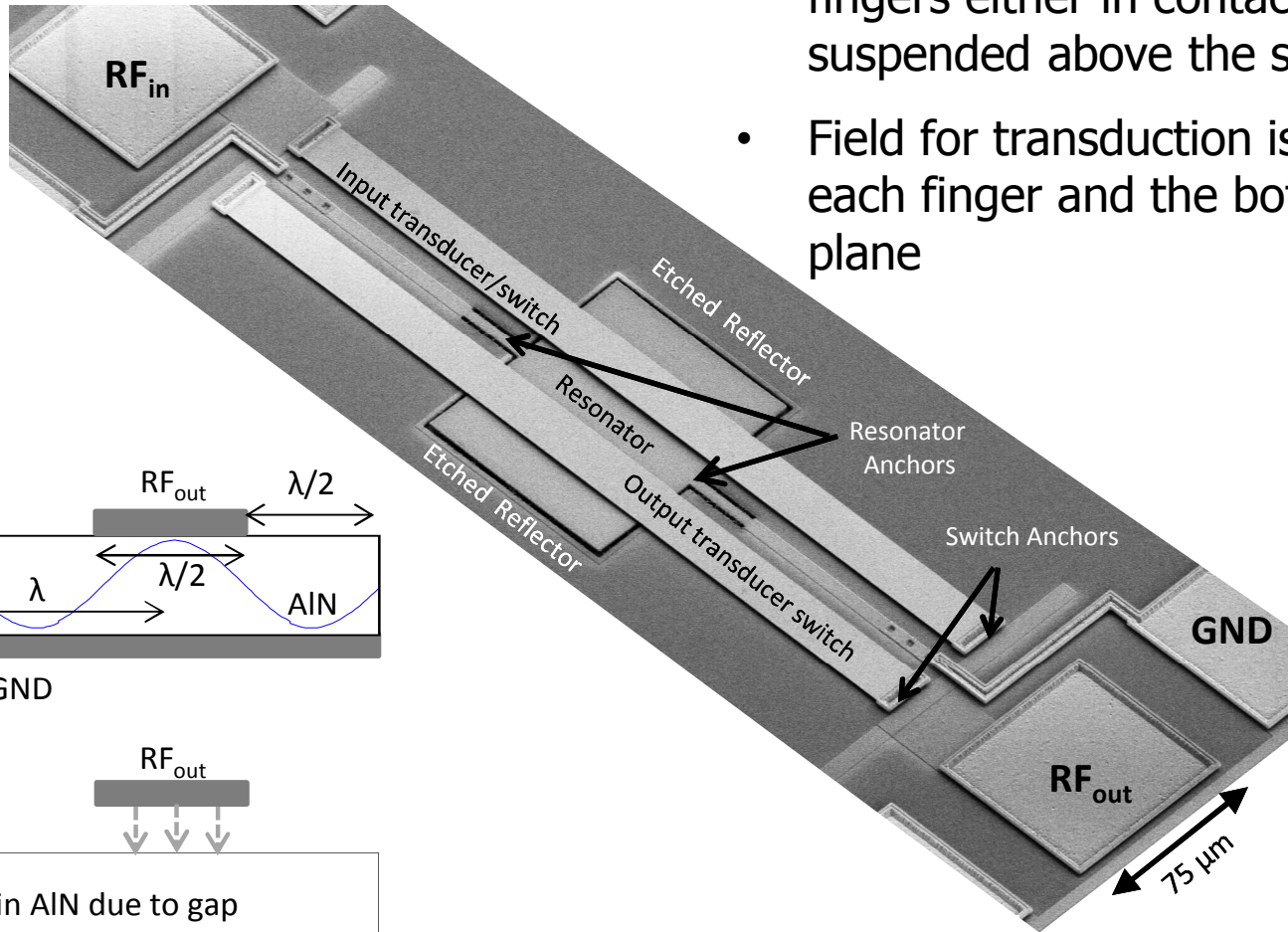
RF FPGA Programmable Filter Approach

- Single Acoustic Structure Covers Multiple Bands and Channels
- Frequency Programmed Using Suspended Electrodes
- Much Smaller Size
- Ultimately Supports a Much Larger Number of Filter Frequencies



On/off switched resonator design

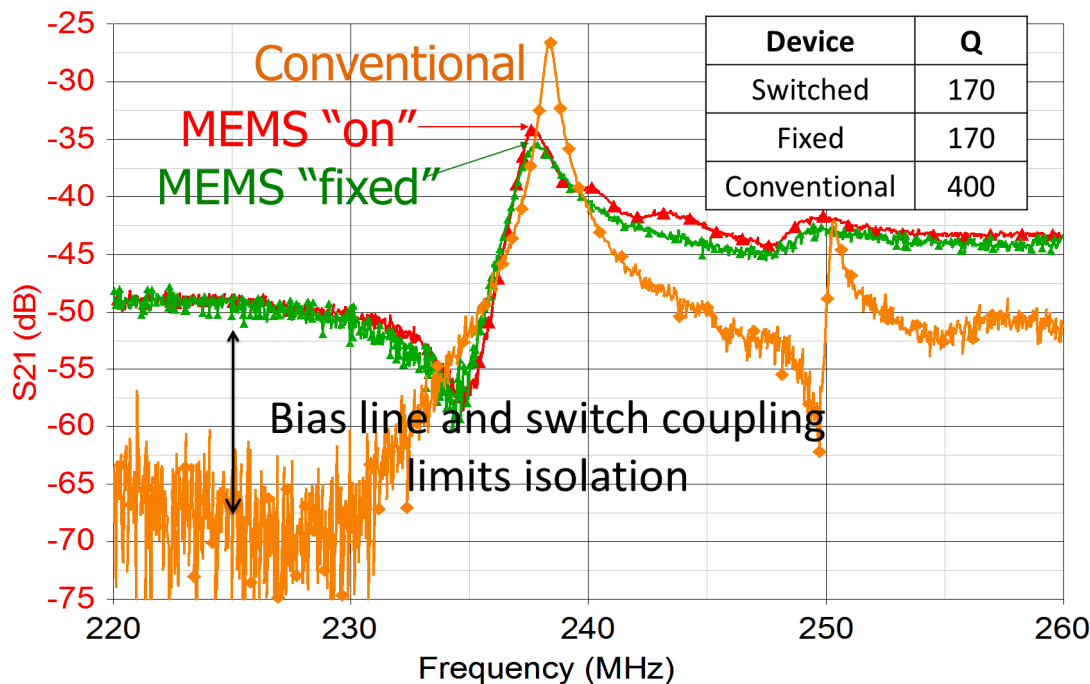
- Two-port single resonator with fingers either in contact or suspended above the substrate
- Field for transduction is between each finger and the bottom ground plane



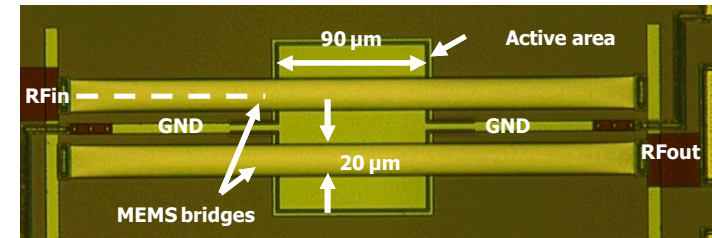


First Results (11/2012): Switched vs. Fixed Resonator

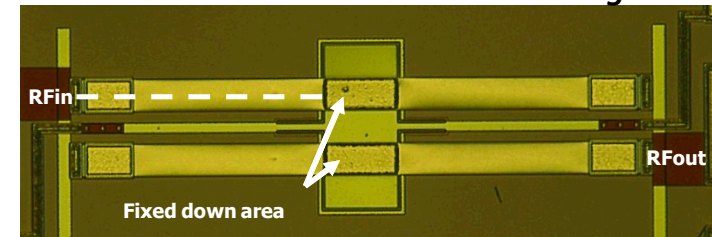
- Both fixed and switched resonator has poorer response than conventional structure
- Isolation of switched structure is inferior to conventional structure
- More discussion later



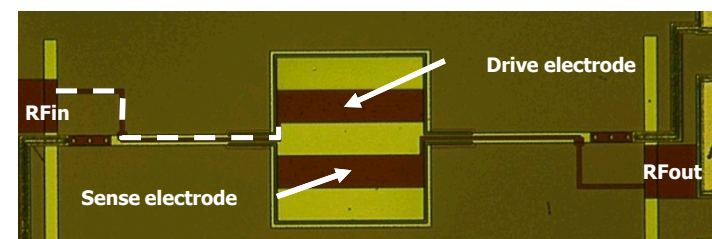
MEMS-Switched Resonator



Resonator with Fixed-Down Active Region



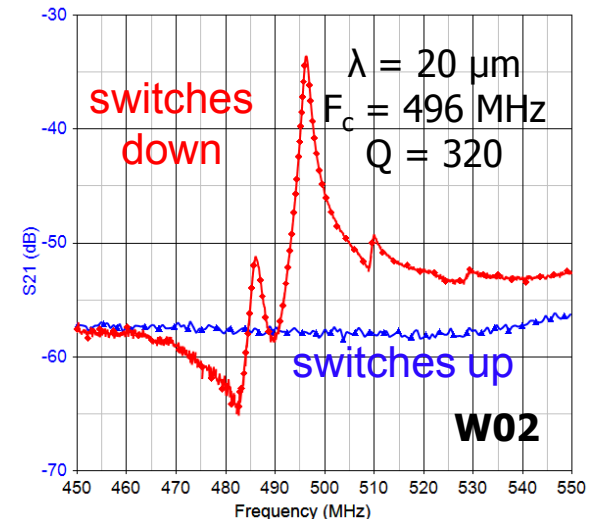
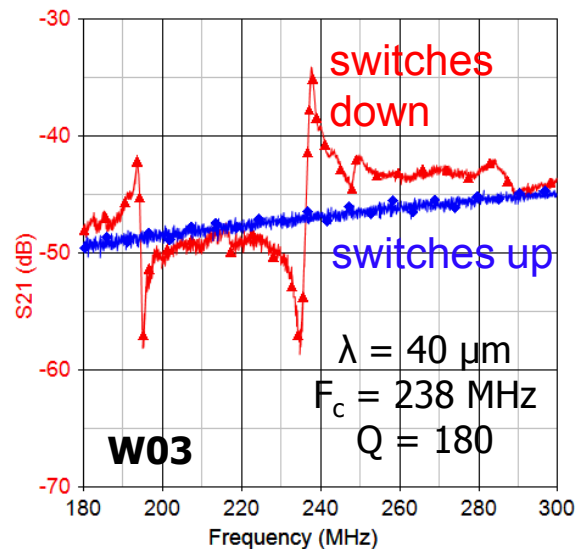
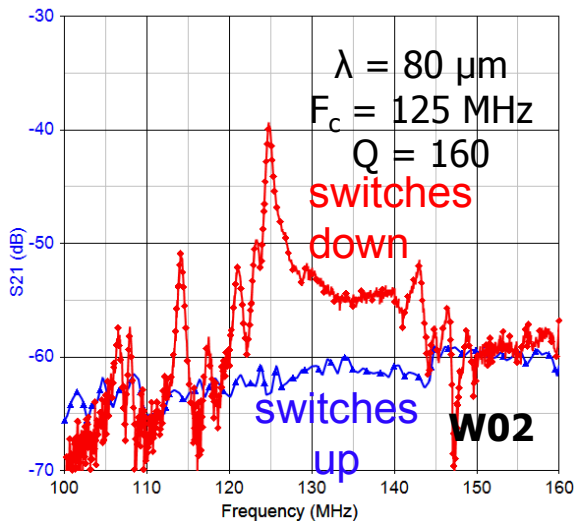
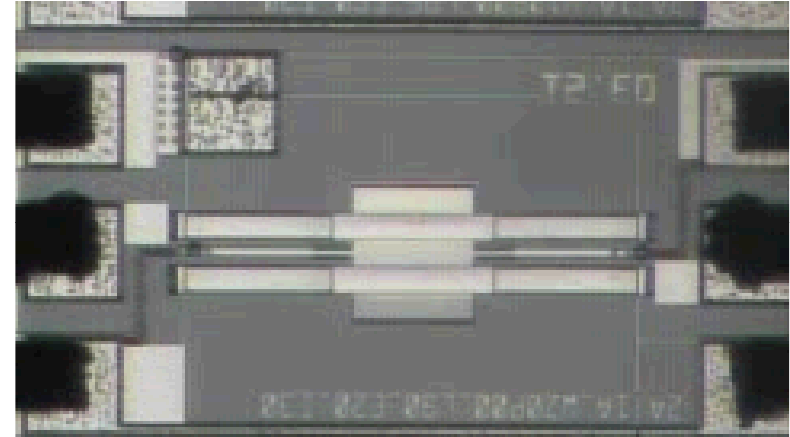
Resonator with Fixed Conventional Feed





Switched Resonators at Three Wavelengths

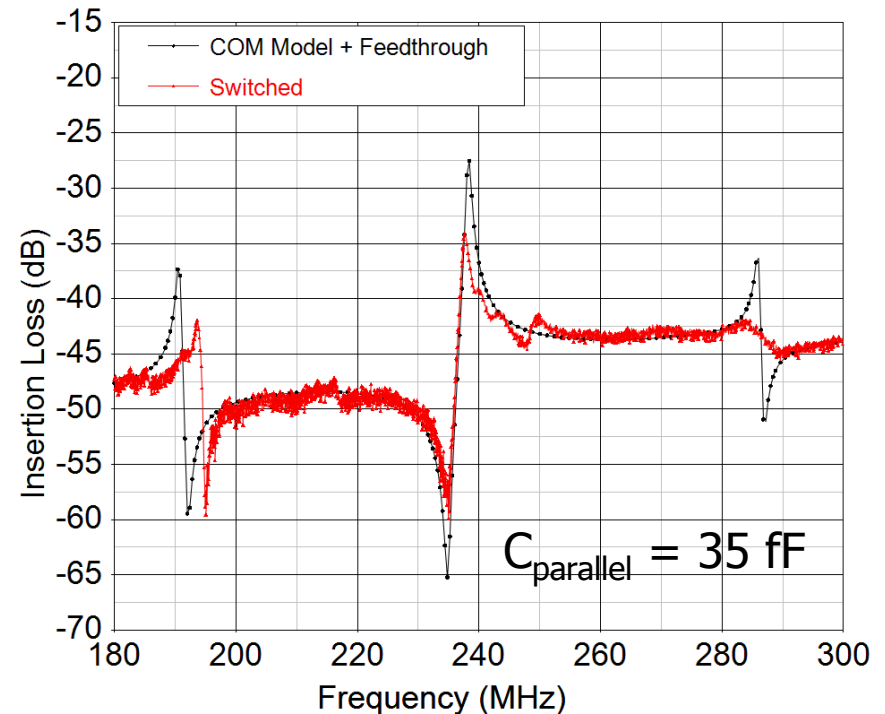
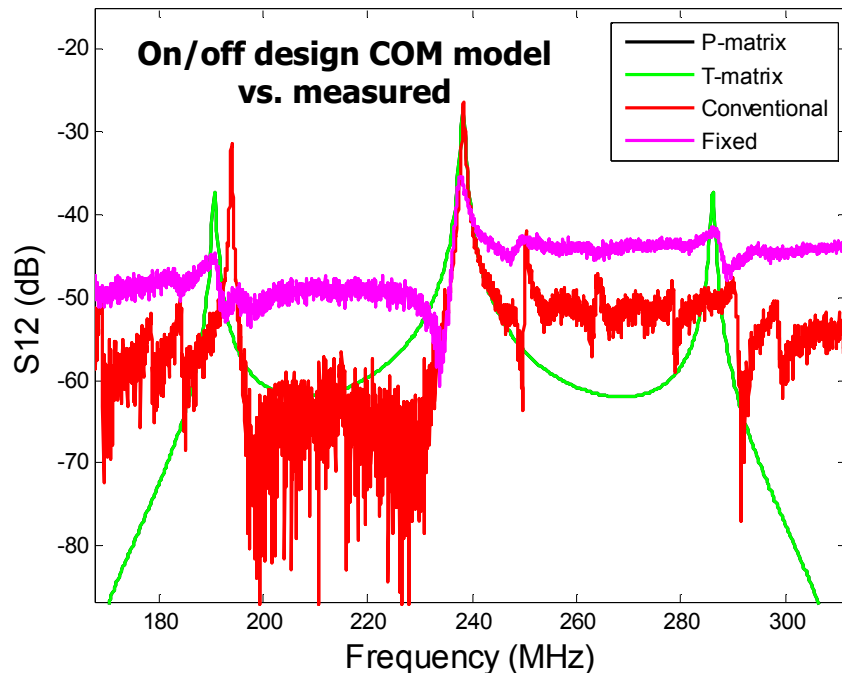
- Switched piezoelectric resonance demonstrated at 125 MHz, 238 MHz, and 496 MHz
- Devices are high impedance to allow demonstration with minimum number of switches
- Q ranges from 160 – 320
 - Appears to increase with frequency (increasing aperture width in λ)





Coupling of Modes Modeling Results

- Coupling of modes modeling accurately predicts on/off design
 - Conventional design predicted by regular COM model
 - Switched case requires addition of feedthrough capacitance for accurate model
 - Does not capture the reduction in Q due to additional damping
 - FEM values were used, except that velocity was adjusted by 1.8%





Fabrication Flow (1)

- Deposit poly-silicon on oxidized high-resistivity Si wafer
- Deposit additional SiO_2 and polish flat to reveal poly-Si island
- Etch opening in oxide, deposit W etchstop, polish flat, and deposit and etch lower TiAl electrode



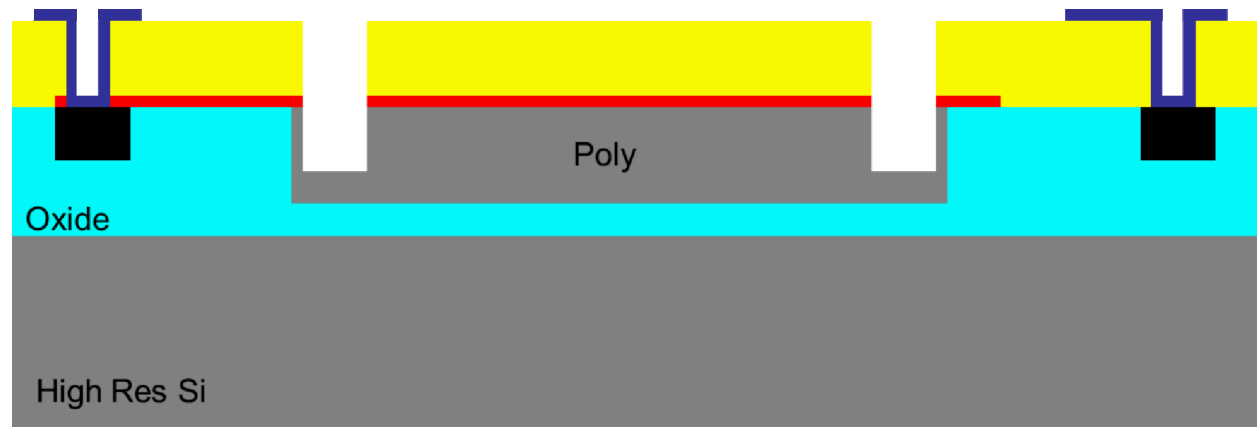


Fabrication Flow (2)

- Sputter deposit AlN piezoelectric layer and etch contact openings to bottom metal



- Deposit and etch resonator TiAl upper electrode; etch release openings through AlN to expose poly-Si sacrificial layer

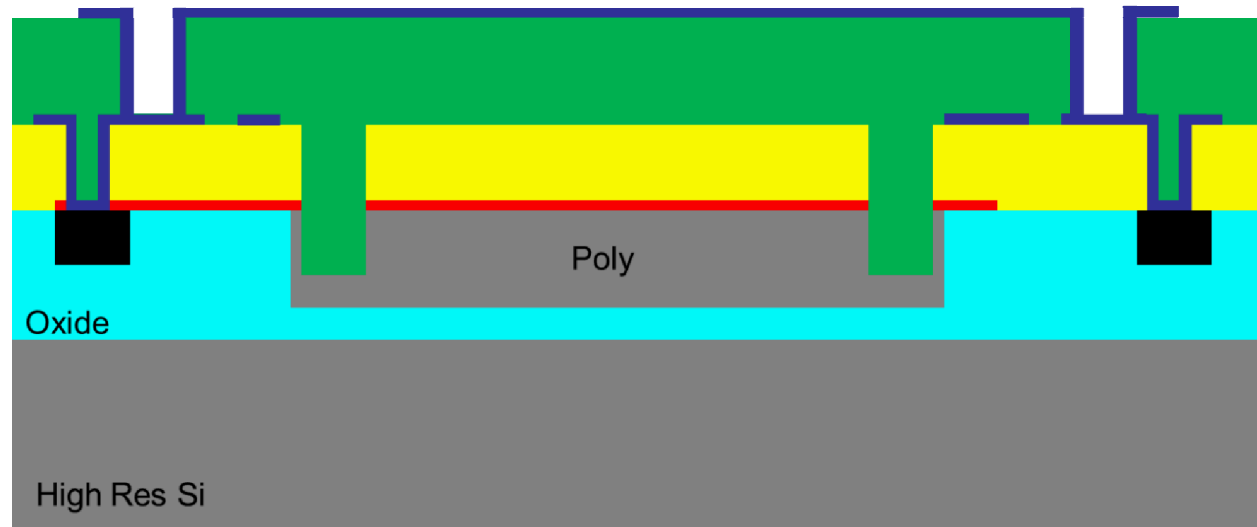
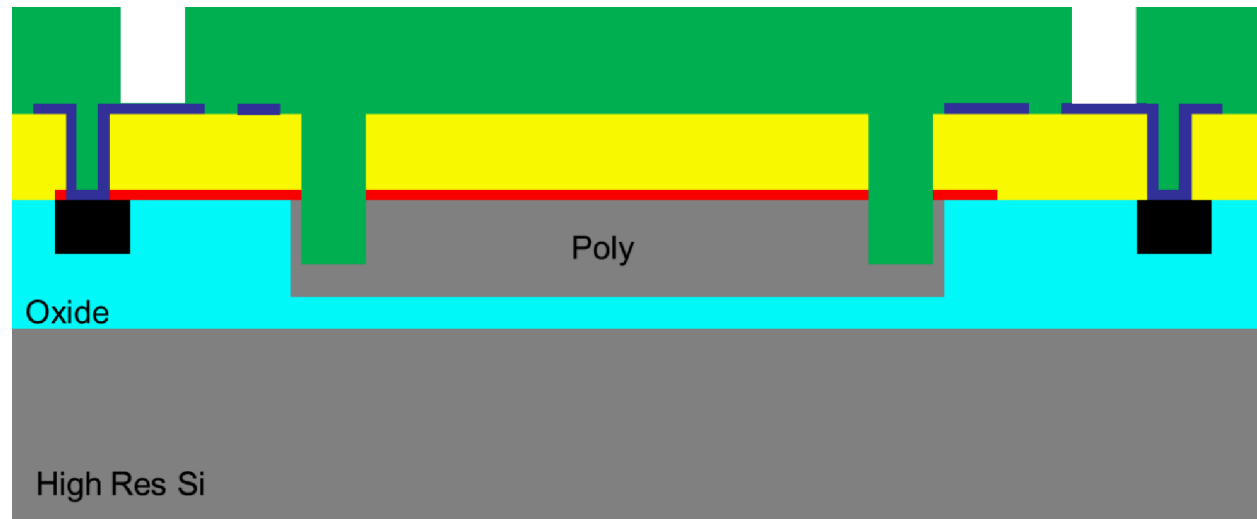


- Other than the MEMS release step, this completes the AlN microresonator structure



Fabrication Flow (3)

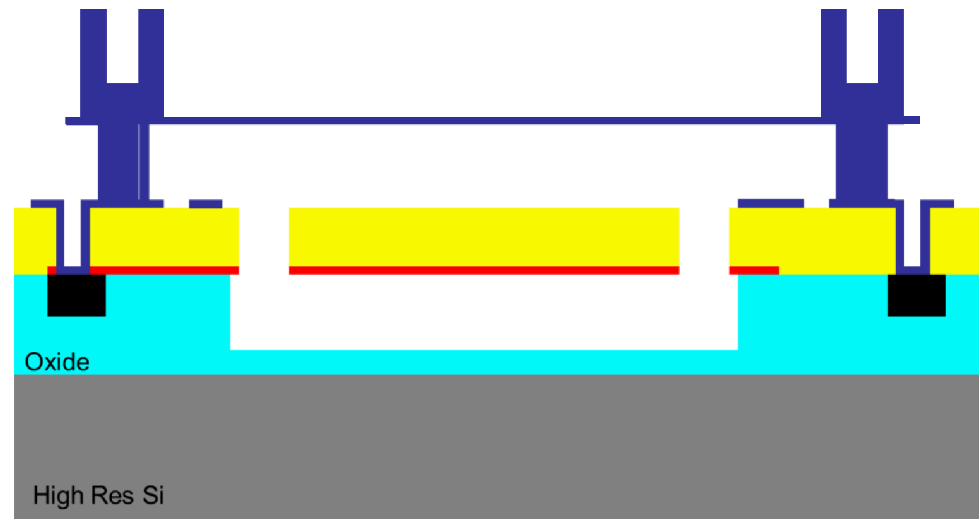
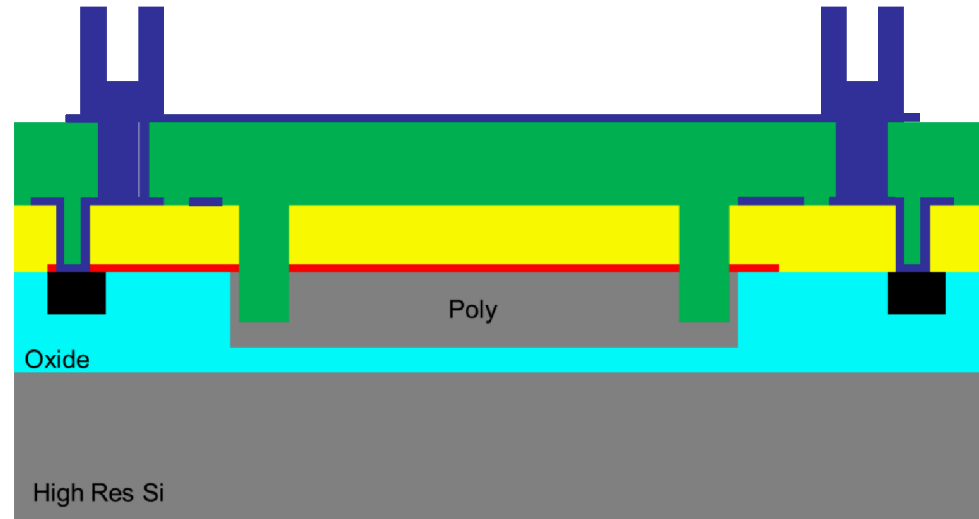
- Deposit, polish, and etch SiN switch sacrificial layer
- Deposit and etch Ti/Al switch bridge metal





Fabrication Flow (4)

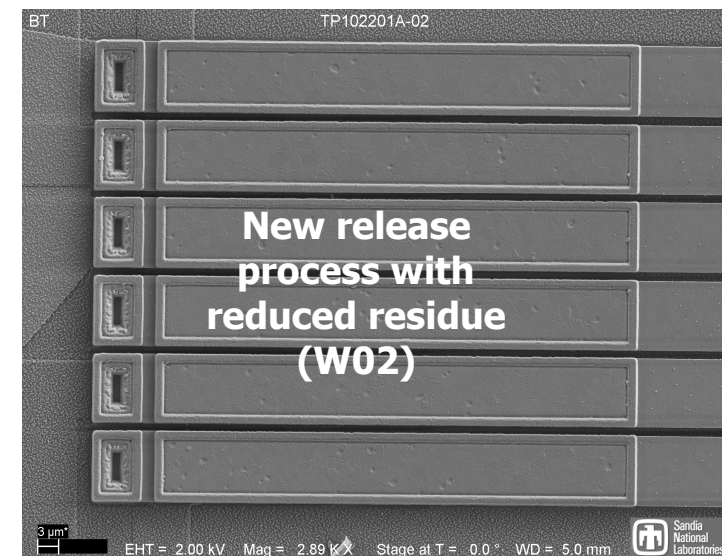
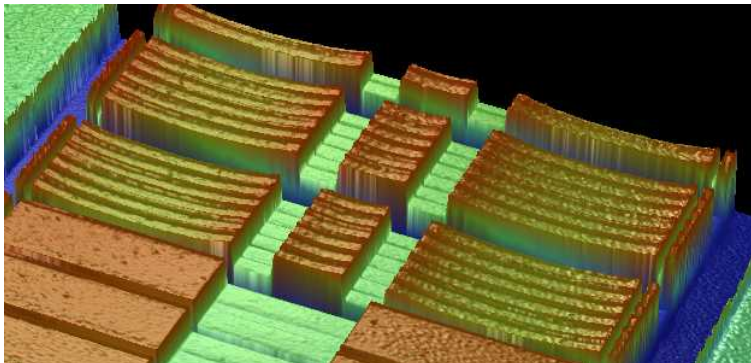
- Deposit and etch thick anchor and beam reinforcement TiAl
- Etch poly-silicon and Si_3N_4 sacrificial layers to release MEMS devices





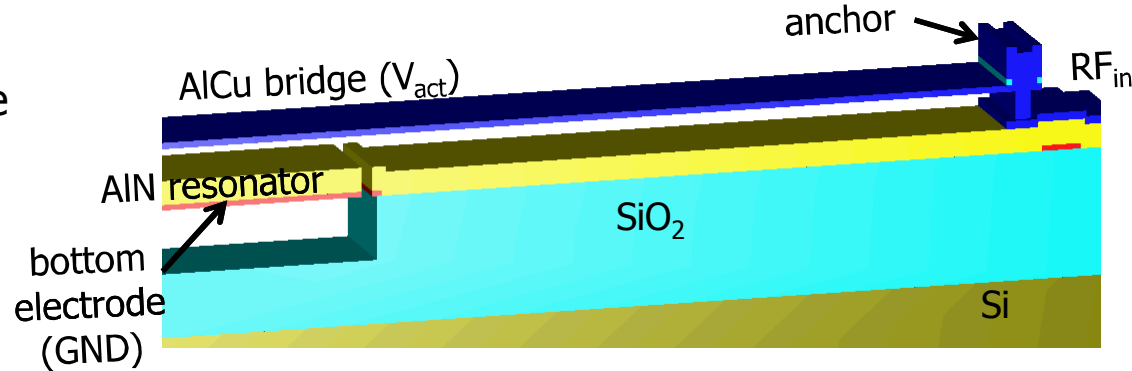
Fabrication Challenges

- **Opening of deep vias in Si_3N_4 stopping on Al**
 - Very difficult etch when nitride thickness $> 1.5 \mu\text{m}$
 - Thicker layers will require alternate etchstop layer over Al (under development)
- **Post-release residue on switches**
 - Lowered device Q and caused switch stiction
 - Traced back to top of SiN sacrificial layer
 - Solved by blanket etch of SiN prior to bridge metal
- **Metal stress in bridges**
 - High residual stress increases pull-in voltage
 - Metal stress causes curvature along reinforced sections



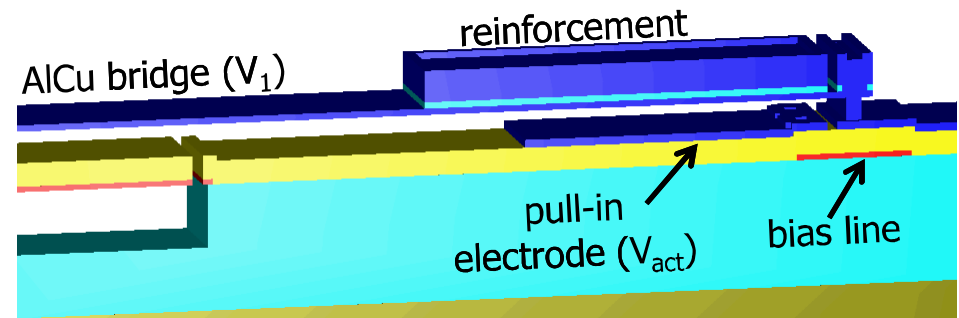
1. Standard capacitive switch

- Pull-down voltage between bridge and bottom electrode
- Simple design, ensures good contact, susceptible to charging, cannot be independently addressed



2. Pull-in electrode near anchor

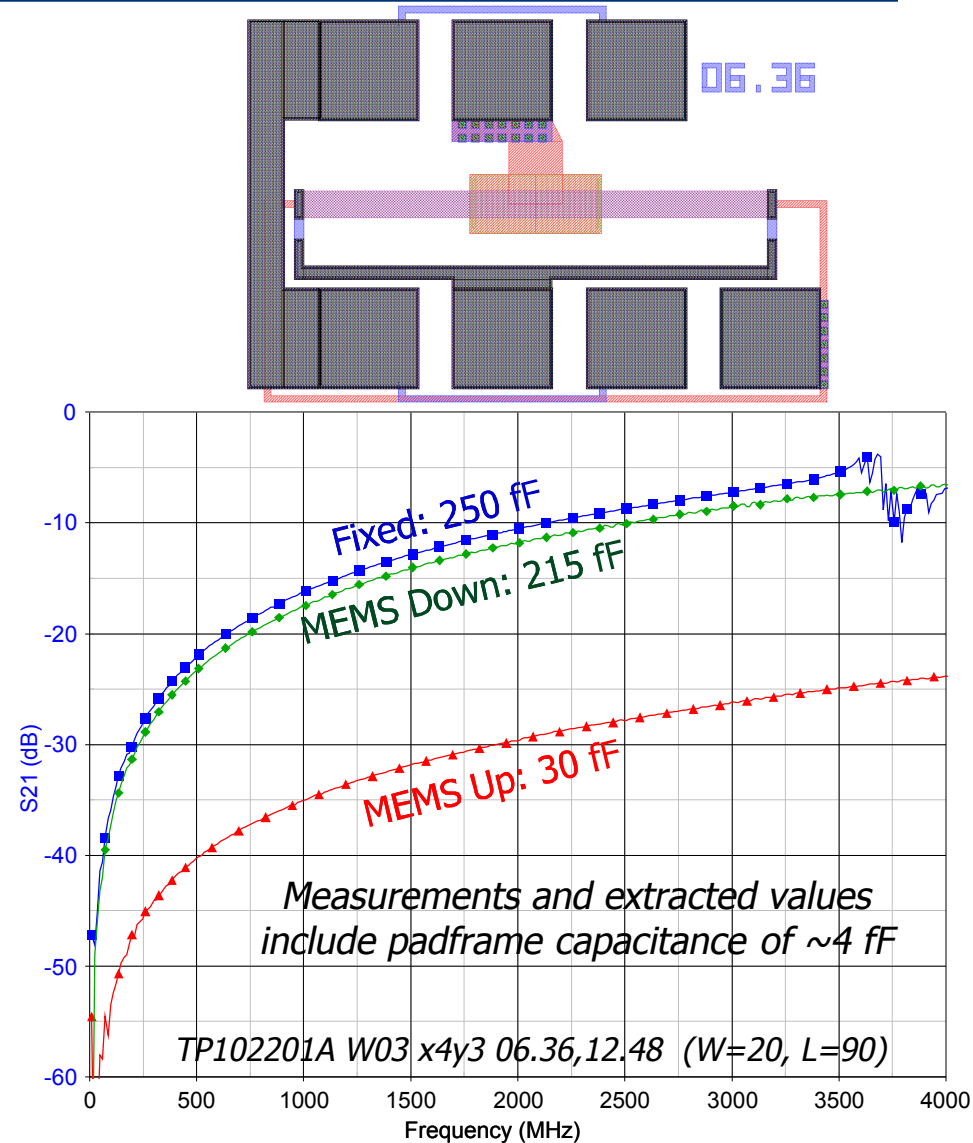
- Less susceptible to charging, separate RF & bias allows individual addressing
- Requires some bridge biasing to ensure intimate contact
- Actuation electrode moved underneath AlN dielectric to prevent electrode shorting in revision of first mask





Capacitive Switch Measurements

- **Measured data from “standard” capacitive switch**
 - Fixed down capacitance density is $0.14 \pm 0.01 \text{ fF}/\mu\text{m}^2$
 - Down-state capacitance is 70-85% of fixed down switch – suggests average gap ranging from 10-30 nm.
 - AlN rms roughness $\sim 2 \text{ nm}$
 - Upstate capacitance is 3x higher than predicted from parallel-plate approximation at intended bridge height
 - Thicker sacrificial layer thickness will reduce up-state capacitance to AlN

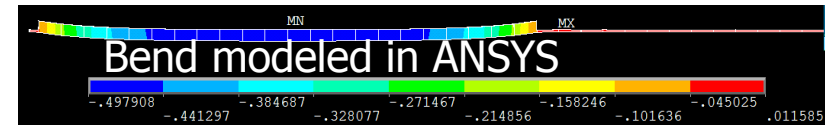
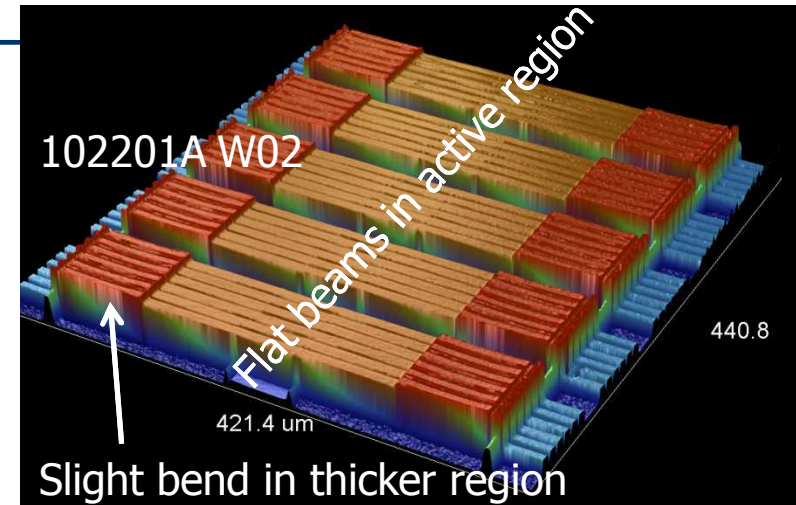




Switch Modeling and Characterization

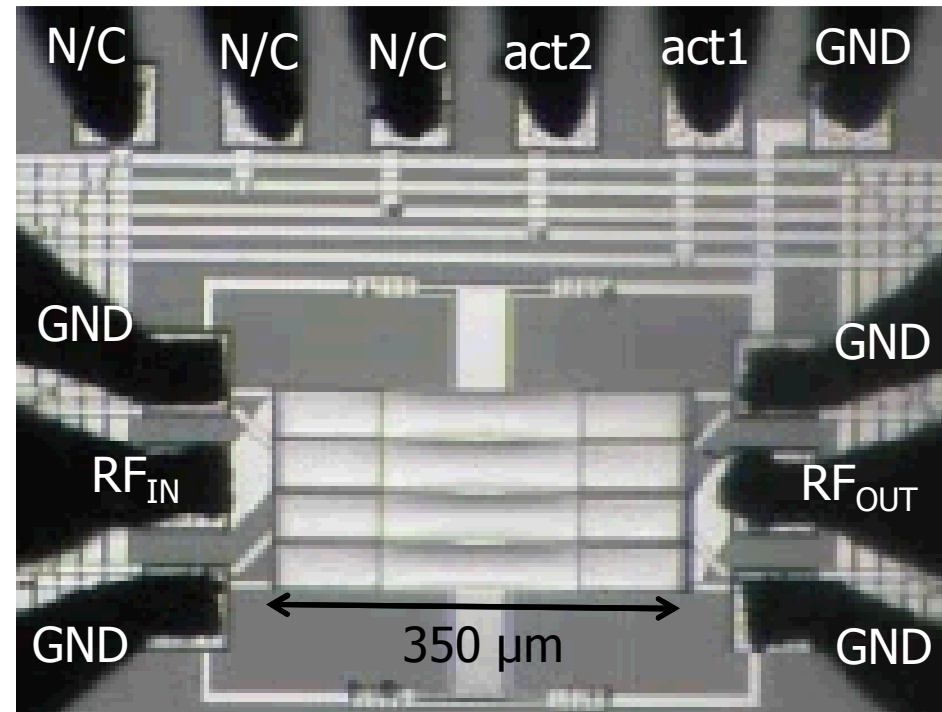
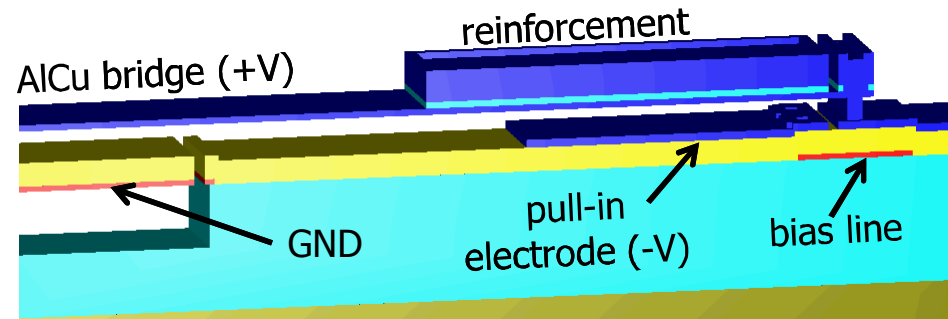
Stress characterization

- Beams are tensile stressed, behaving more like "strings" than beams
- Some curvature in thicker sections due to tensile stress and non-uniform cross-section ($r_c=9\text{mm}$)
- The stress state observed in the first lot is adequate for this work, but causes limitations with making intimate contact
- Switches used for Bragg reflectors have reinforced center section – additional challenges with curvature



Addressable Switch Actuation

- Required for complex programmability of transducers and Bragg reflectors
- Biasing conditions relative to bottom ground electrode
 - Bridge: +
 - Edge pull-in electrode: -
- Both bridge and edge electrode must be biased to close switch
- Example transducer shown
 - Bridge connections: 1+2, 3+4
 - Edge electrodes connections: 1+3, 2+4
 - Bridges at 0V or +8V
 - Edge electrodes at +8V or -16 V
 - Switches actuate when both the bridge and the edge electrodes are biased





Acoustic Interface Physics and Model Building Block

Model:

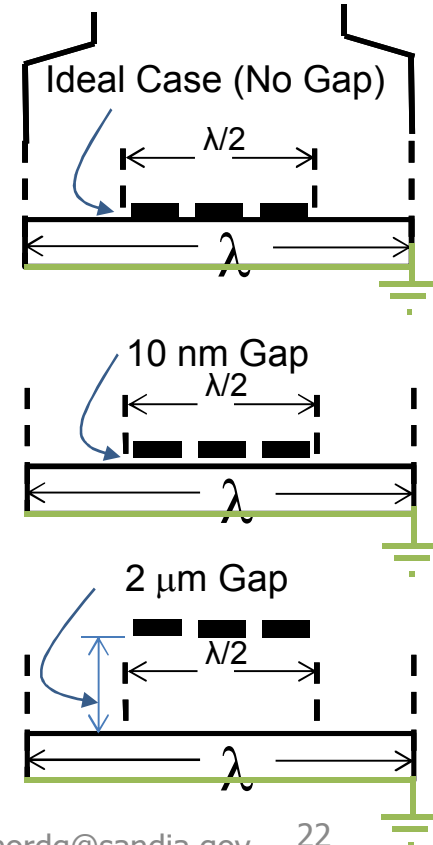
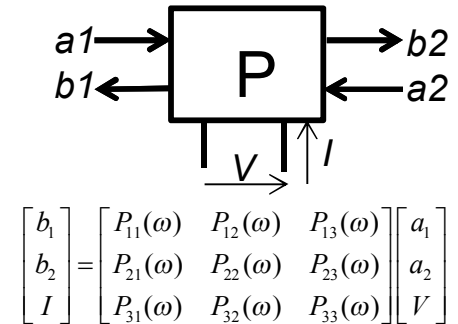
- The mixed scattering matrix (P) is computed from the COM parameters and represents the simplest periodic device building block.
- What happens to the COM parameters for **active** (10nm) and **inactive** (2μm) fingers:

Case	Velocity	Reflection	Acoustic Coupling	Static Capacitance
No Gap	1	1	1	1
10 nm Gap (active)	1.05	0.81	0.98	0.88
2 μm Gap (inactive)	1.06	0.11	0.0011	0.11

Takeaways:

- Imperfect contact to the AlN causes negligible decrease in transduction.
- Uniform imperfect contact causes significant reduction in reflectivity.
- Breaking the fingers into three does not impact transduction

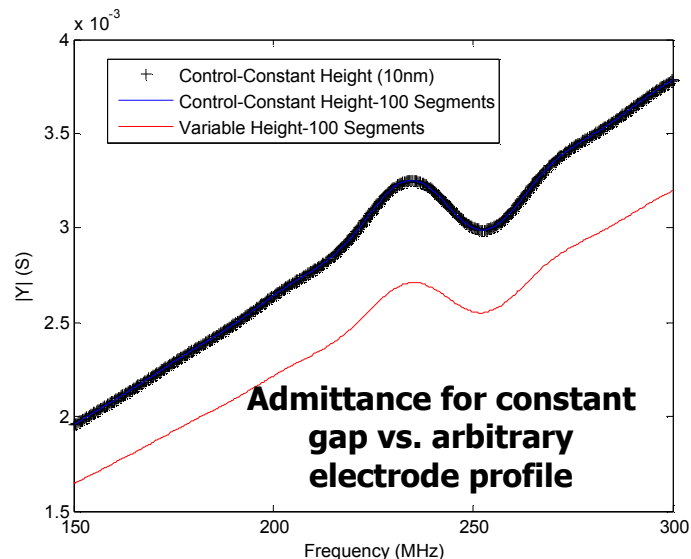
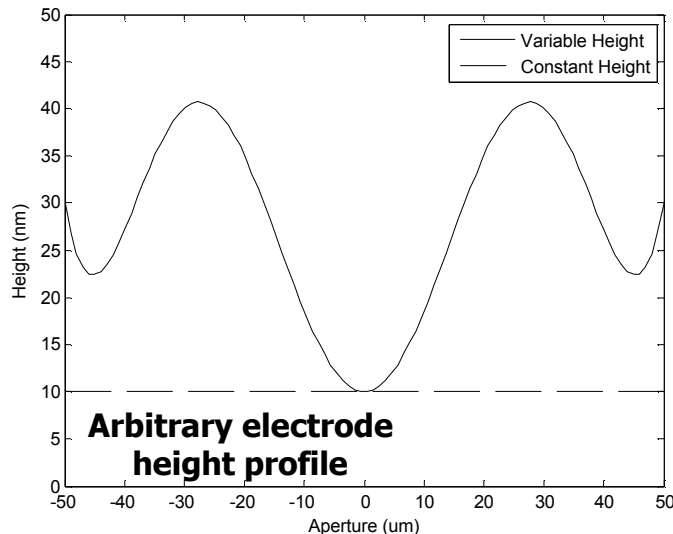
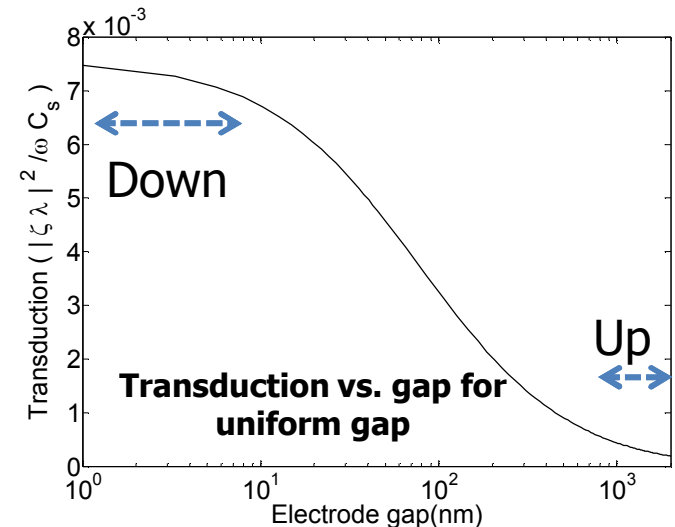
Mixed Scattering Matrix





Imperfect and Non-Uniform Finger Contact

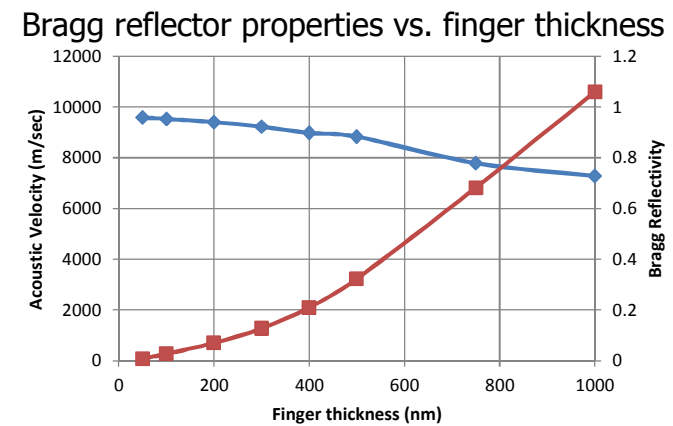
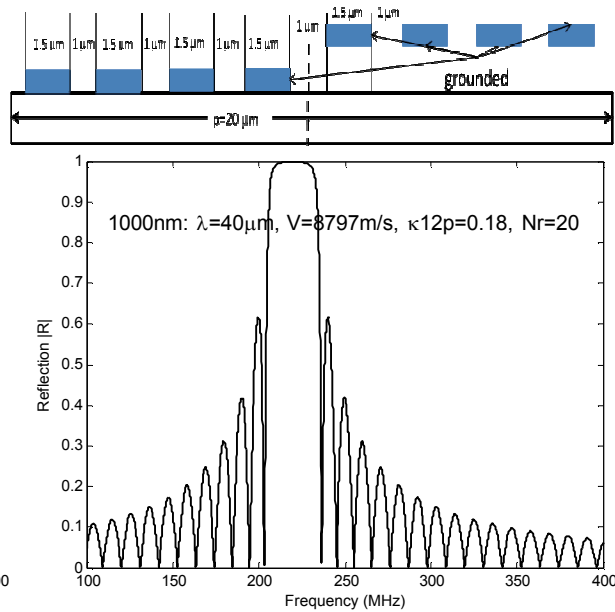
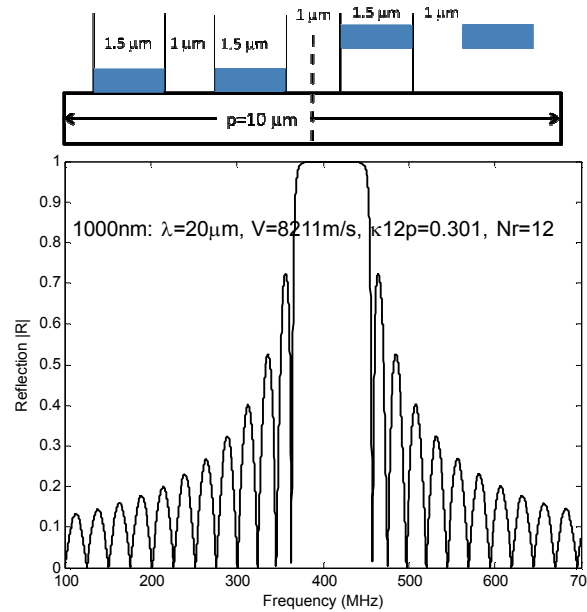
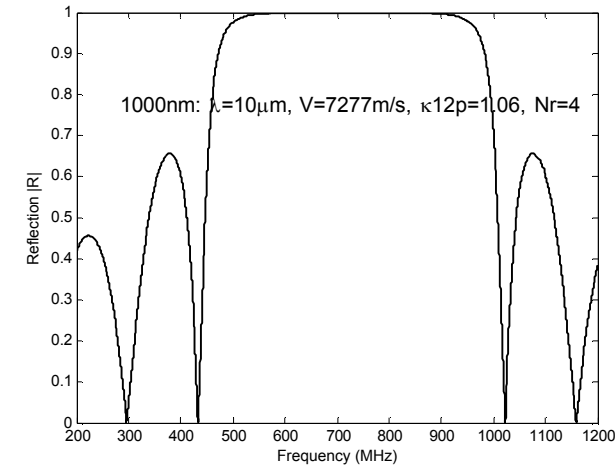
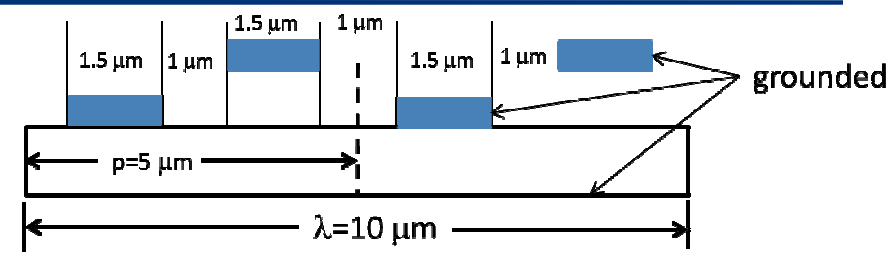
- Modeling to determine the impact of imperfect and non-uniform contact on the performance of a transducer electrode
- Imperfect contact: transduction is within 90% of fixed down value for nm-scale gaps
- Non-uniform contact: admittance and transduction is similar to uniform gap of same average distance
- For Bragg reflectors, loss of contact significantly drops reflectivity (reflection is primarily mechanical)





COM Modeling of Tunable Bragg Reflectors

- **Bragg Reflector Unit Cell**
 - 1.5 μm fingers on 2.5 μm pitch
 - Shortest wavelength: 10 μm ($F \sim 800$ MHz)
- **Modeling Results**
 - Loading from thicker finger slows down wave by $\sim 20\%$
 - Bragg reflectivity depends upon mechanical contact

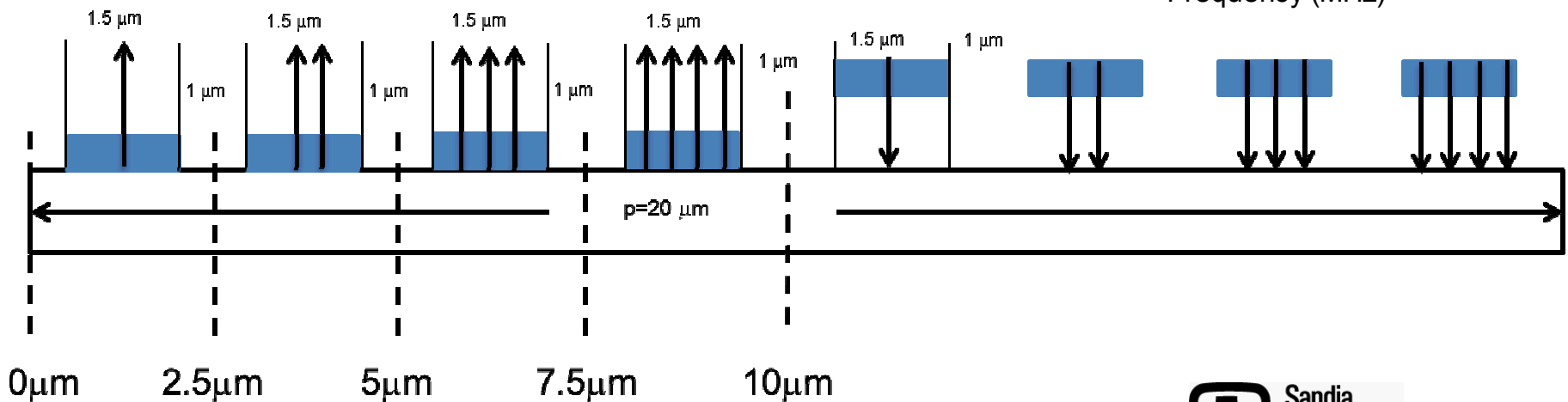
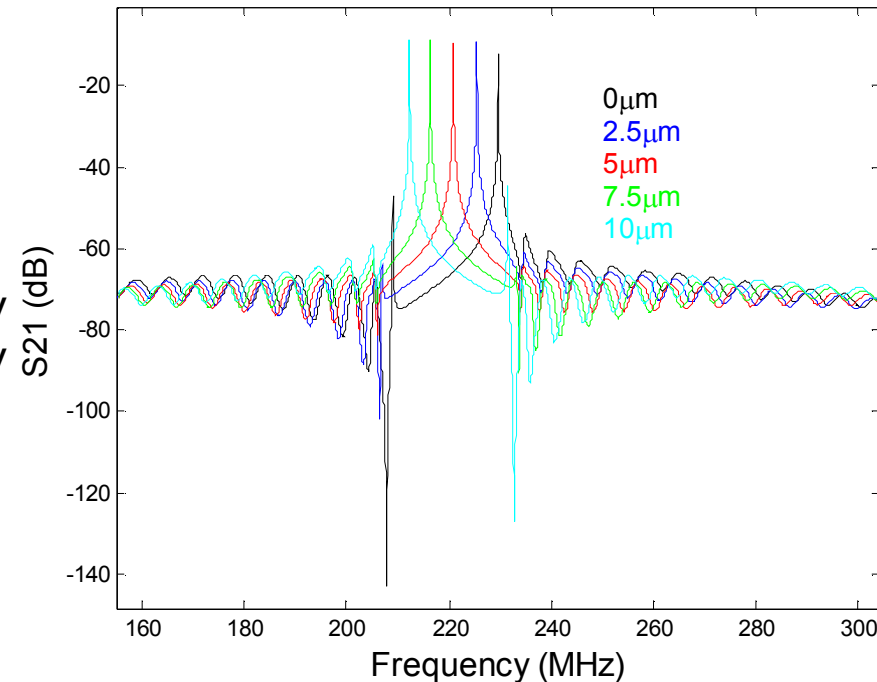




Tuning by Varying Gap from Transducer to Reflector

- **Can tune cavity length by tuning point along array where reflector begins**

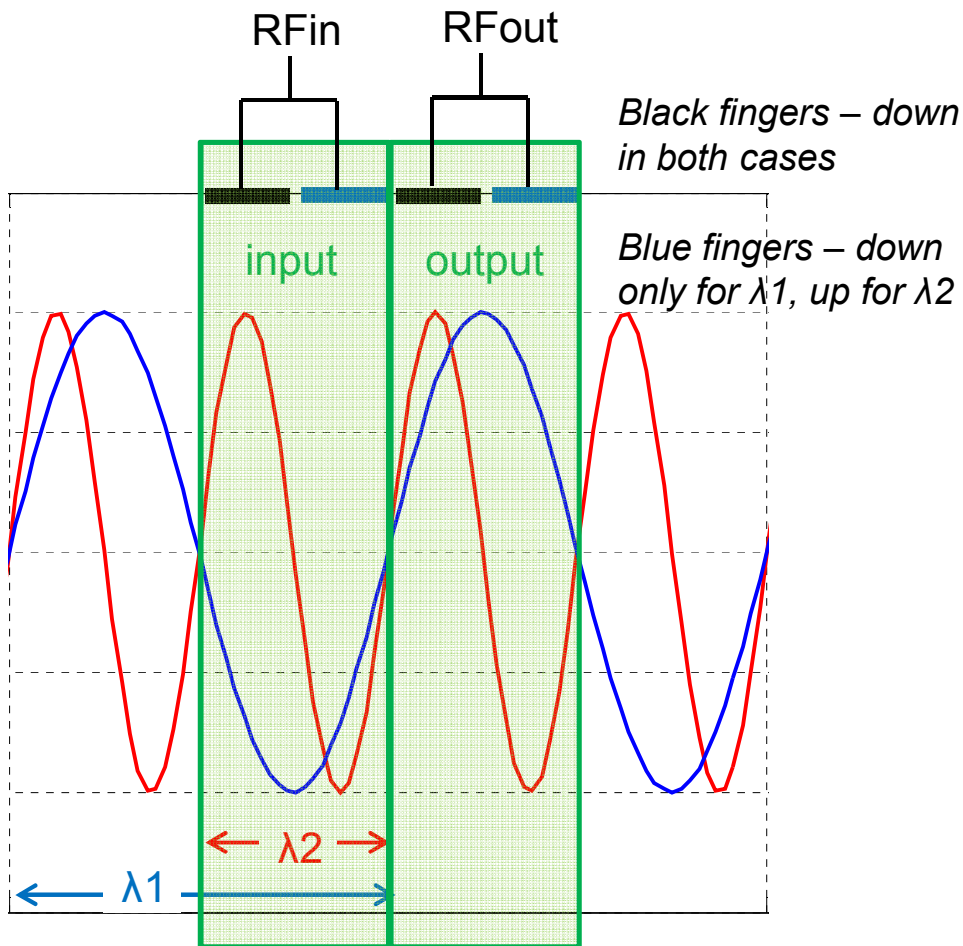
- Example: 40 μm wavelength with 2.5 μm fine-tuning
- Transducers and Bragg reflector are sufficiently broadband to allow for varied center frequency
- May also be able to take advantage of difference in velocity with mechanical loading





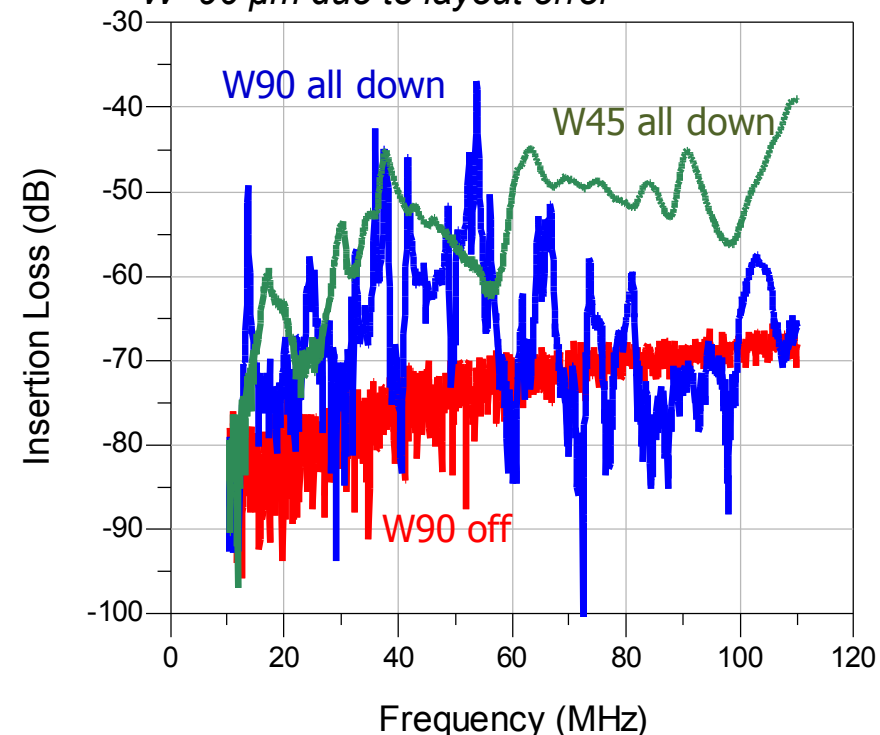
F/2F Design w/ Etched Reflector

- Switch between a frequency and second harmonic
- Designs fabricated and tested but demonstrate poor response
 - Inadequate aperture width + larger (40 μm) fingers



Marked difference in Q between $W=90\ \mu\text{m}$ and $W=45\ \mu\text{m}$ – difference in aperture width

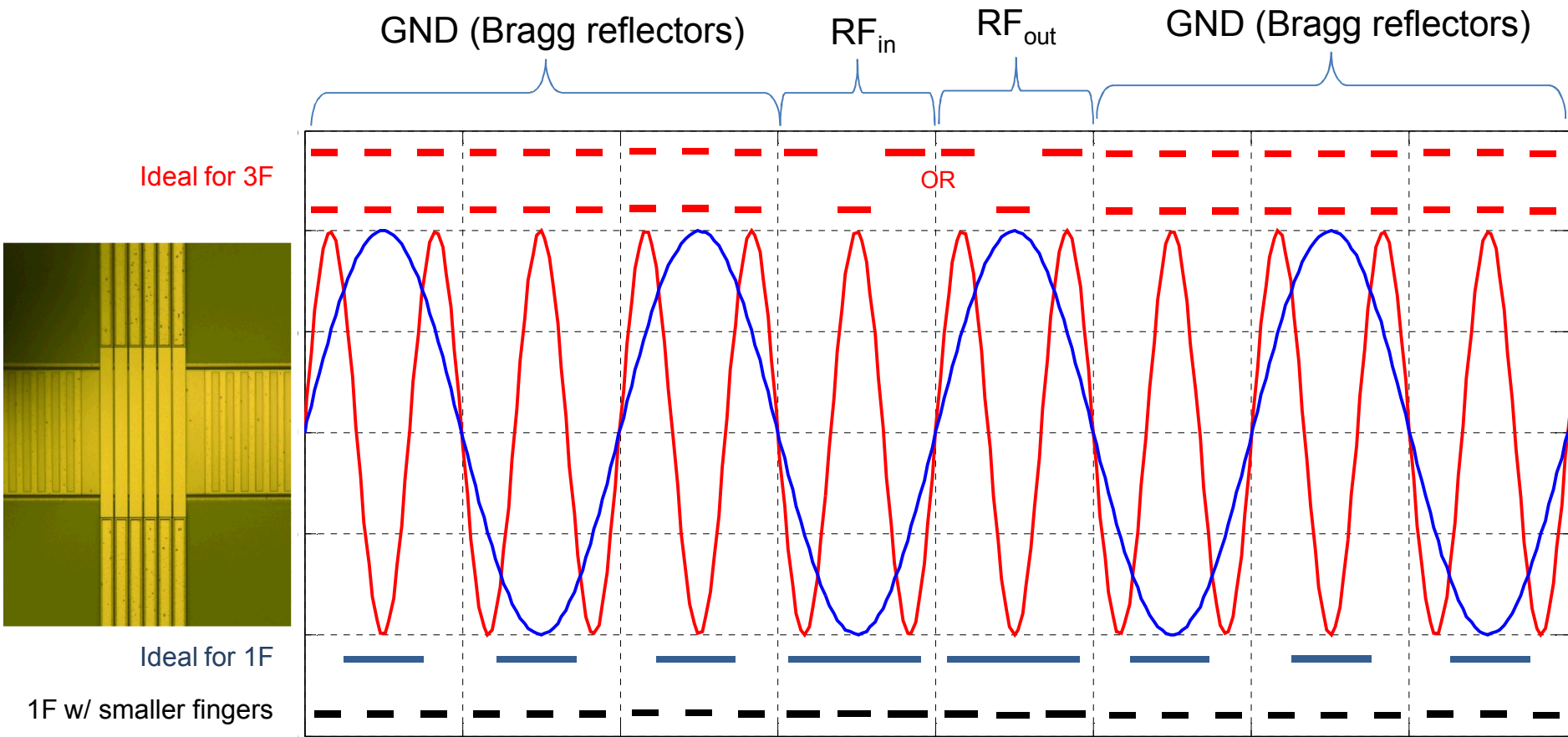
Unable to actuate fingers separately on $W=90\ \mu\text{m}$ due to layout error





F/3F Design w/ Bragg

- Design with switched transducer fingers and fixed Bragg fingers
- Colored lines show fingers that are in contact with substrate for given operation
- Bragg is not reflective enough – probably not in contact with AlN due to stress





What is Limiting Q?

- Q values

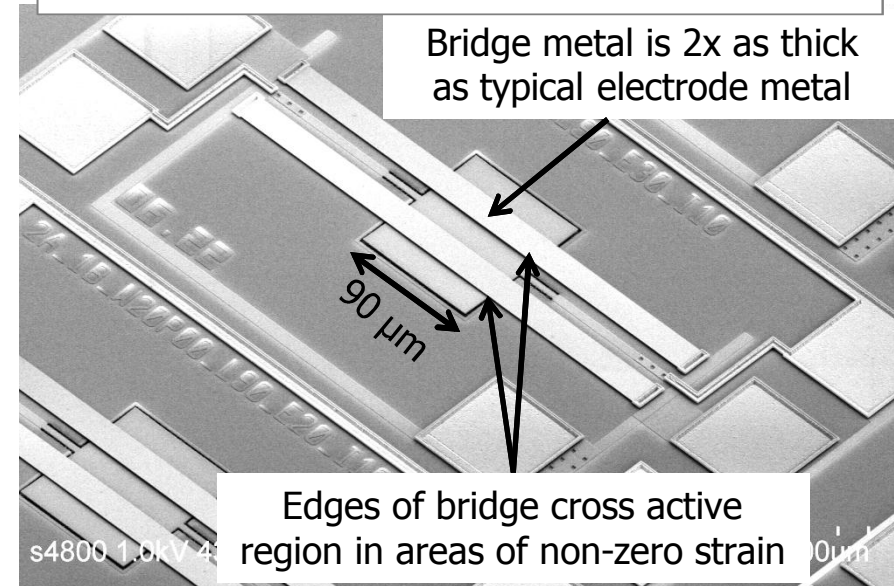
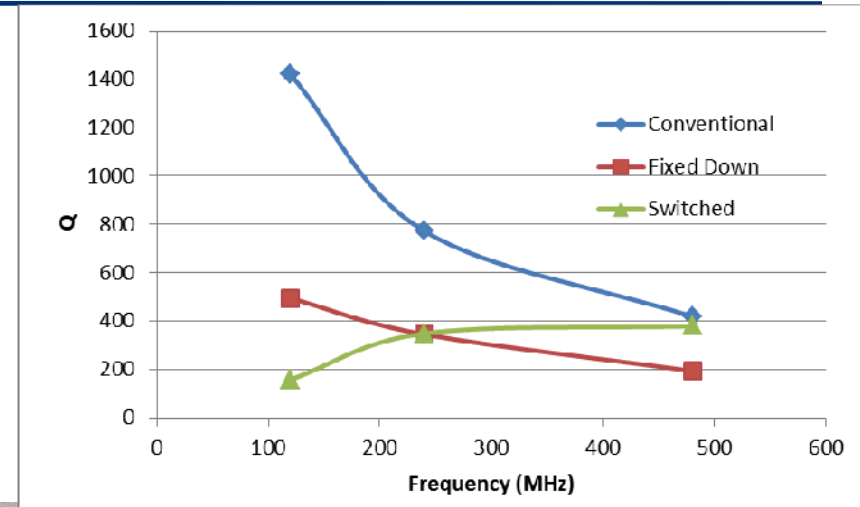
- Q of switched structure is ~ 300 at 240 MHz
- Q of conventional structure is ~ 800 at 240 MHz
- Typical Q of ideal AlN device is ~ 1800

- Other trend to consider

- Q of switched structure **increases** with frequency
- Q of conventional structure **decreases** with frequency
- Suggests that anchor losses, rather than interface losses, are dominating

- Why is the switched device Q lower than the conventional device Q?

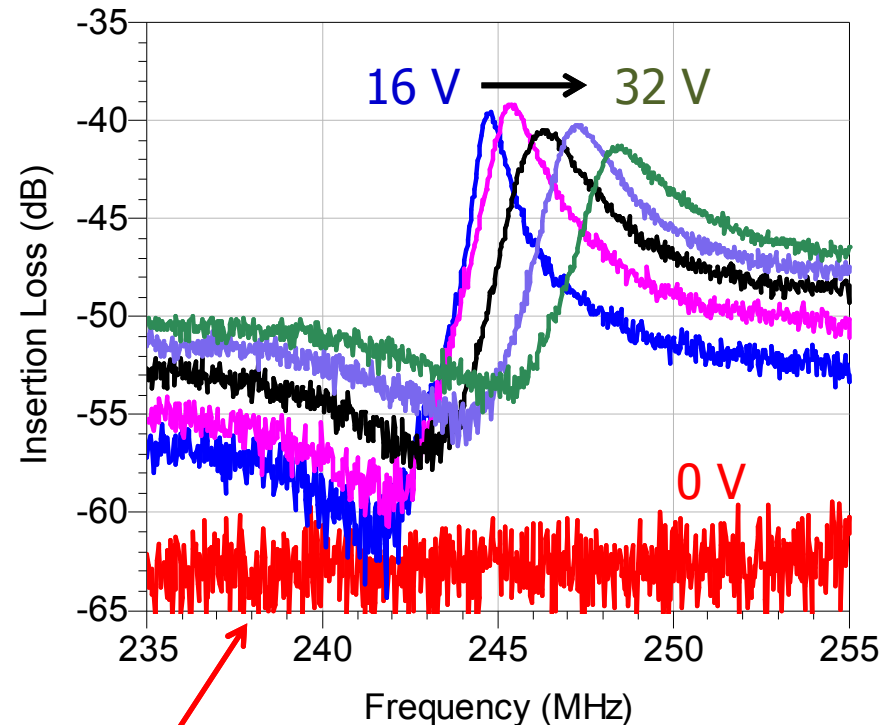
- Damping due to thicker bridge electrode
- Damping due to bridge edges crossing active region at points of non-zero strain (strain null is at the center of the bridge)
- Only using two electrodes limits transduction





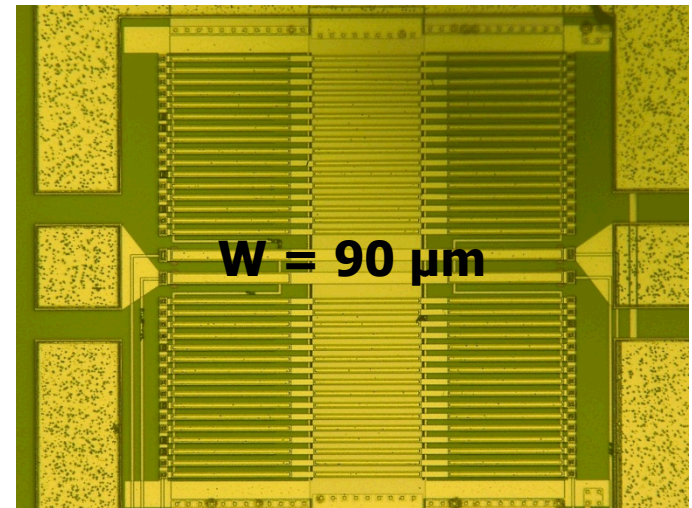
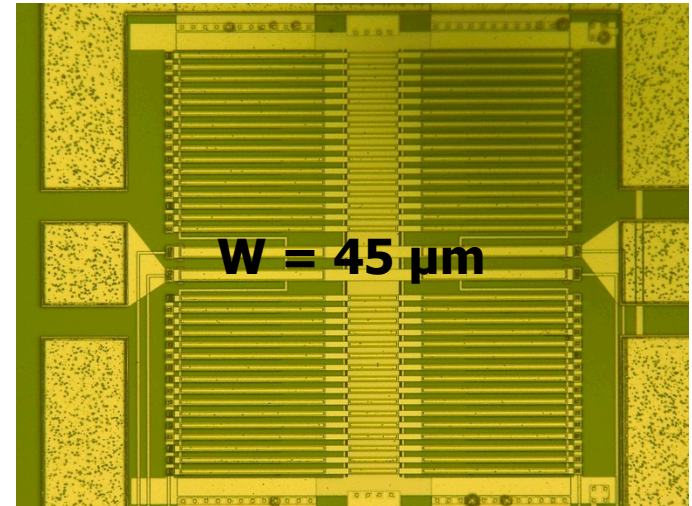
Voltage Tuning

- **Observed ~ 0.2 MHz/V tuning after pull-in on two-switch designs**
 - If understood, offers additional tuning mechanism
 - Provides hints about factors limiting Q
- **Trends**
 - Q **decreases** with increasing voltage
 - Resonance **increases** with increasing voltage
- **Implications**
 - Both effects appear to be related to applied force
 - Increased voltage \rightarrow increased contact \rightarrow increased damping
 - AlN membrane may be bending / flexing and changing strain in piezoelectric material



Improved isolation from electrode redesign

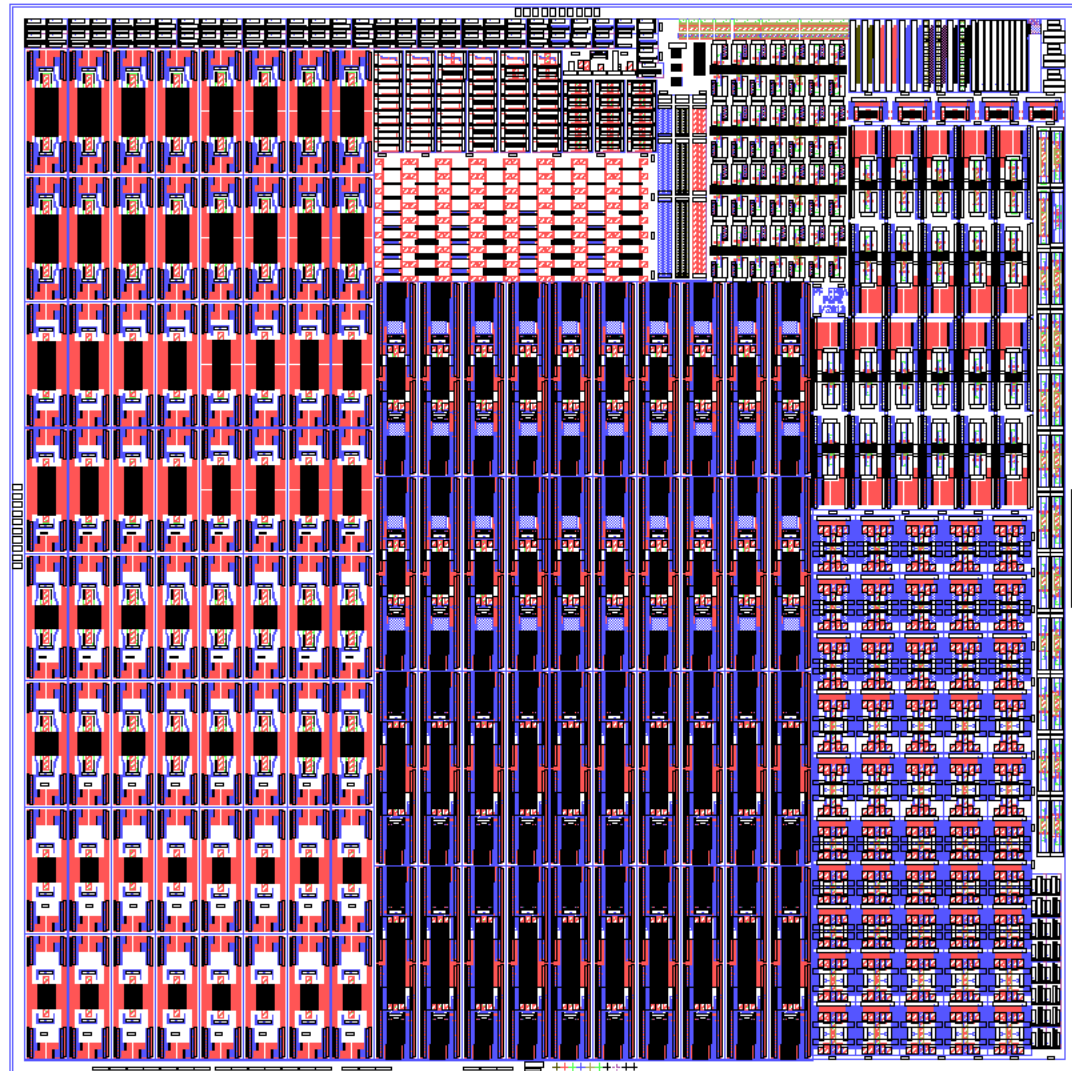
- **Increase aperture width**
 - Loss is caused by damping along edge of resonator
 - Wider aperture will have smaller impact from bridges crossing edges of structure
- **Increase transduction area**
 - Multiple fingers to lower device impedance
- **Novel switch designs**
 - Switches anchored to AlN membrane rather than crossing gap
 - Switches optimized to reduce anchor losses
- **All of these approaches are being explored on a wafer lot that is currently in fab**





Maskset Currently in Process

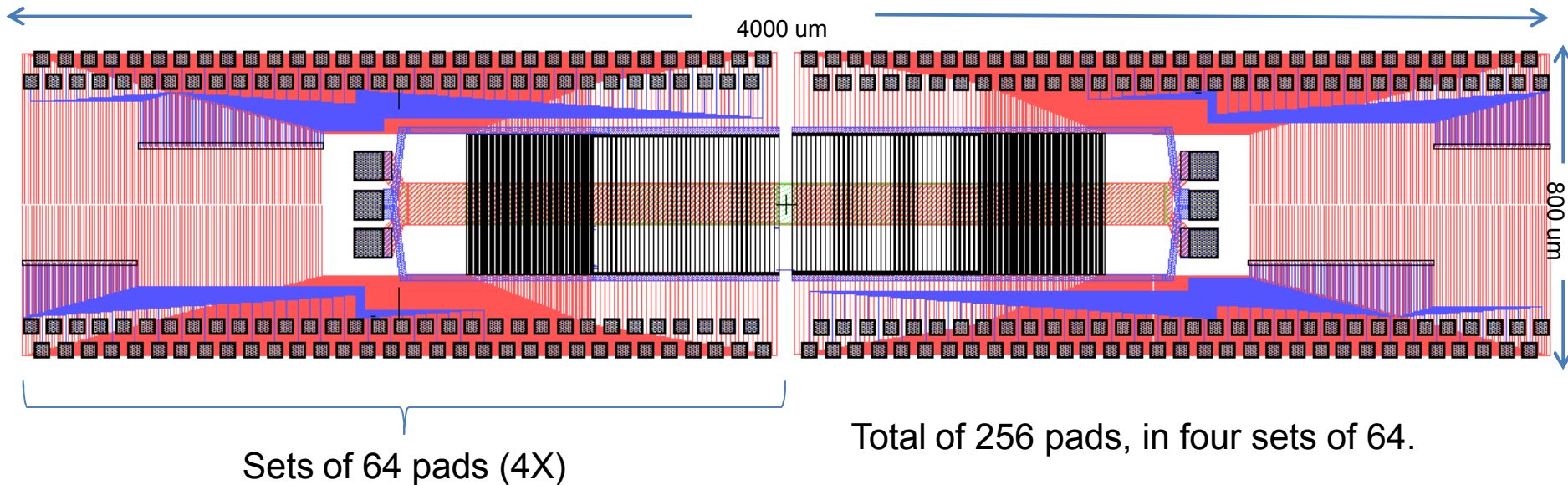
- **Applied lessons learned from first fab/test cycle**
 - All devices use a wider aperture
 - More multi-finger devices
 - Reflectors tuned for lower velocity in Bragg gratings
- **Highly reconfigurable filters**
 - 40 finger transducers
 - 64 finger reflectors
- **Transducer and reflector test structures**
 - Bragg coupling structures
 - Bragg fine-tuning structures
- **Fab Due end of August**





High-Order Transducers and Reflectors

- **Addressing and testing filters with 40-electrode transducers and 64-element reflectors will be a challenge**
- **Test Plan: 256-pin circuit-board based probe card with Labview-addressed switch matrix to drive individual pins**
- **Switch yield and reliability will also be a challenge**





Major Results

- **Piezoelectric transducers can be turned on and off using MEMS**
 - The foundation of the activity, demonstrated from 120 MHz – 500 MHz
 - Scalable to at least 2 GHz ($W = 2.5 \mu\text{m}$)
 - Transduction is relatively robust with small gap between AlN and switch beam
- **Contact and metal thickness play an important role for Bragg reflectors**
 - Mechanical effects are primarily responsible for reflection – need intimate contact.
 - Thick metal increases reflection, lowers velocity – different pitch for transducer and reflector
 - Bragg-based designs on current mask did not work because they were not thick enough
- **Anchor damping and mass loading are limiting Q in current designs**
 - Q depends on aperture width to decrease influence of anchors.
 - Larger electrodes with more fingers will reduce loss of devices
- **Switches with 3 actuation terminals allow individual addressing**
 - Building block for more complex filters and structures.
 - Some ground-to-bridge bias required to pull electrodes flat on AlN



Comparison to BAA Objectives

- **Can We Aggregate Designs From Five Different Applications?**
 - We believe that this approach can be used to aggregate at least five designs.
 - Need additional effort in designs for higher Q and lower loss (in process)
- **Where Have we Achieved the Goals?**
 - Have achieved Stage I goal of demonstrating functional piezoelectric switching of resonators using MEMS switches.
- **Where Have we Fallen Short?**
 - We have not achieved Q values consistent with those of fixed resonators. Achieving this will require redesign of the MEMS switch structure and filter to mitigate anchor losses and metal damping.
 - We have not demonstrated a filter that switches in frequency with good Q. The new designs that are in fabrication are expected to meet this goal.



Application Potential

- **Switched / reconfigurable filters in the 10 MHz to 2 GHz range**
 - Upper frequency determined by manufacturability of switch: $\lambda(2 \text{ GHz}) \sim 4 \text{ } \mu\text{m}$
 - Higher frequencies may be achievable with longer-wavelength materials or submicron dimensions
 - Lower frequency determined by overall size of device: $\lambda(10 \text{ MHz}) \sim 800 \text{ } \mu\text{m}$
 - Other modes or approaches may allow for lower frequencies but have not been considered
- **Bandwidths of less than "a few percent"**
 - Lower bandwidth determined by Q of device
 - Upper bandwidth determined by material properties ($k_t^2 Q$ product)
 - Other materials may increase this space
- **Power levels TBD (but probably not "Watts")**



Shortcomings of Approach

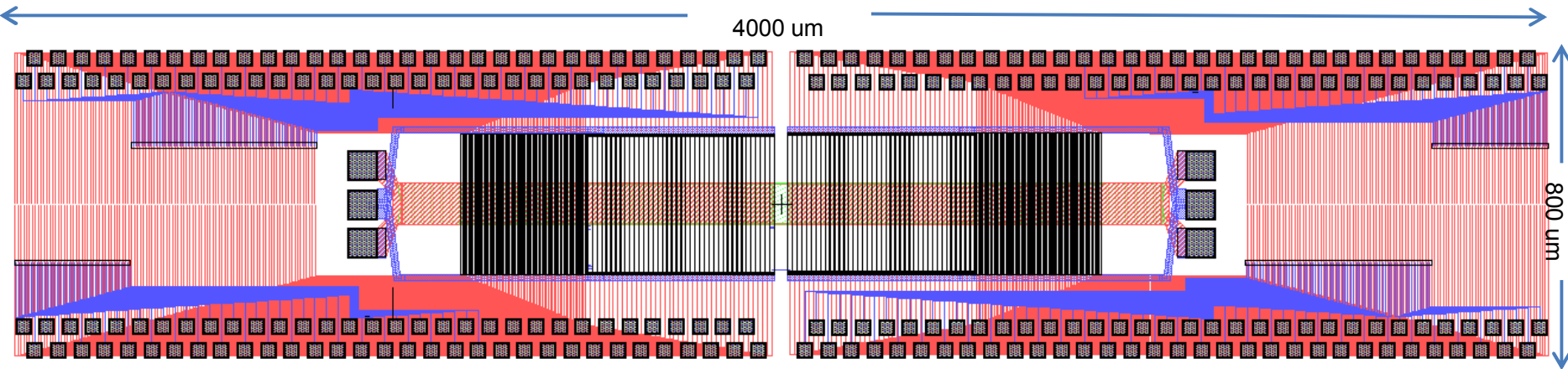
- **The usual challenges associated with MEMS technologies**
 - Yield – basically two MEMS processes merged
 - Reliability – dielectric charging and metal fatigue
 - Packaging – clean hermetic microenvironment required for long-term deliverables
 - ***THESE ISSUES HAVE BEEN ADDRESSED BY CAPACITIVE SWITCH SUPPLIERS***
- **Reduced Q due to damping from switch structure**
 - Thicker metal + anchor losses presenting higher losses than standard structure
 - Switch redesign to eliminate edge crossings are expected to improve these losses
 - ***WIDER APERTURE, MORE FINGERS, ALTERNATE SWITCH DESIGN CAN IMPROVE***
- **Control complexity**
 - Control of individual fingers requires many bias lines – suggests integration with electronics for intelligence, decoding, and high-voltage drivers.
 - ***MEMS CO-INTEGRATION WITH ELECTRONICS IS IN PRODUCTION***



Path To Phase Two Goals

- **Is There a Clear Path to Phase Two Goals from Where We Are?**
 - Phase Two goals: Demonstrate theater programmability of filters meeting requirements of five relevant bands.
 - The current design concepts can meet these goals, especially in conjunction with higher-Q switches
- **What Changes Do We Anticipate to the Program Plan?**
 - Accelerated integration of the MEMS switch with the resonator from Stage II into Stage I at DARPA's request – did not pursue fixed filters as a result
 - Expect focus of Stage II to shift towards modeling and testing to improve the Q and response of the filters.

- **Stage I (through 9/12/2013)**
 - Complete current wafer lot (new designs)
 - Preliminary testing of devices on new wafer lot
- **Stage II Goal: Real-time programmable filter covering five states**
 - Exhaustive testing of new designs and matching to models
 - Improve Q and filter responses
 - Two fabrication and test cycles anticipated





Summary

- **Demonstrated piezoelectric switching using MEMS switches**
 - Appears there are no fundamental flaws with this approach
- **Demonstrated integrated MEMS resonator + MEMS switch process flow**
 - Capacitive switches may also allow EM filter tuning, switching, and impedance matching
- **Demonstrated on/off switched single resonators at frequencies from 120 MHz to 480 MHz with Q's up to 300+**
 - Key effort in Stage II will be improving the Q and filter performance
- **Modeled filter structures and identified key parameters for transducer and reflector fingers**
 - Applied learning to designs that are still in fabrication
- **This approach is viable for introducing reconfigurability to piezoelectric resonators and filters**